

### **IN THE SPECIFICATION**

**Please delete the paragraphs beginning on page 2, line 4, starting with and including the heading, Summary of the Invention, through page 2, line 17 before the heading, Brief Description of the Drawings.**

**Please insert the following paragraphs beginning on page 6, line 22 before the current paragraph of the original specification beginning on page 6, line 22:**

An embodiment includes apparatus for a method of forming a film on a substrate that includes activating a gas precursor to deposit a material on the substrate by irradiating the gas precursor with electromagnetic energy at a frequency tuned to an absorption frequency of the gas precursor. The electromagnetic energy can be provided by an array of lasers. The frequency of the laser beam is selected by switching from one laser in the array to another laser in the array. The laser array may include laser diodes, one or more tunable lasers, solid state lasers, or gas lasers. The frequency of the electromagnetic energy is selected to impart specific amounts of energy to a gas precursor at a specific frequency to activate the gas precursor.